

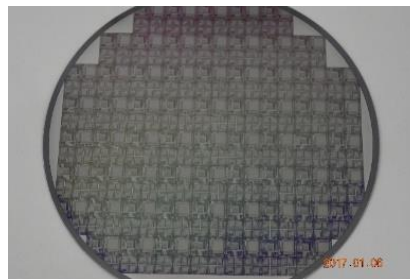
Deposited Wafer and Patterned Wafer

We also offer the service for various Film deposition and Pattern making on both 8inch and 300mm wafers.

<Film depositing>



<Pattern making>



*Our service characteristics of Film deposition and Pattern making

• Possible Film deposition types are shown below.

Category	Production method	Type of film
Oxide	Thermally oxidized film	Thin & Thick thermally oxidized film
	LP-CVD	LP-SiO ₂ , HTO, LP-TEOS
	PE-CVD	PE-SiO ₂ , PE-TEOS, HDP etc.
	Spin coating	SOG
	Annealing	RTO
Nitride	LP-CVD	LP-SiN
	PE-CVD	PE-SiN
Silicon	LP-CVD	Poly-Si, Amorphous-Si
Photo/Resists	Spin coating	G-line • I-line • KrF • Ar
Metal	Sputtering	Al, Ti, Ta, Cr, Cu, W, ITO etc.
	Coating	Ti, Ni, Au, Cu etc.
	CVD	W-Si

- We can make the reticle mask for patterning by request.
- We can make 90nm size Hole patterns and Line/Space patterns for 300mm Wafers.

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